Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
Li	25876	deposit\$3 near12 (SiN (silicon adj2 nitride) Si3N4 "Si.sub.3N.sub. 4" "Si.sub.3 N.sub.4" "SiN?sub.?")	USPAT; EPO; JPO	OR	OFF	2004/11/18 11:49
L2	4265	1 and (steam wet pyrogenic pyrogenically water "H.sub.2O" "H.sub.2 O" "H.sub.2/O.sub.2" "O. sub.2/H.sub.2" ("H.sub.2" near1 "O.sub.2") (hydrogen near1 oxygen)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 heat\$3 bak\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/18 11:32
L3	1082	(SiN (silicon adj2 nitride) Si3N4 "Si.sub.3N.sub.4" "Si.sub.3 N.sub. 4" "SiN?sub.?") near12 (steam wet pyrogenic pyrogenically water "H. sub.2O" "H.sub.2 O" "H.sub.2/O. sub.2" "O.sub.2/H.sub.2" ("H.sub.2" near1 "O.sub.2") (hydrogen near1 oxygen)) near12 (oxidiz\$3 oxidis\$3 oxidation anneal\$4 heat\$3 bak\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/18 11:32
L4	475	1 and 3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/18 11:32
L5	354	4 and @ad<"19990422"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/18 11:33
L6	103	4 and @rlad<"19990422"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/18 11:33
L7	372	5.6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/18 11:33
L8	10526	(gate adj (dielectric insulat\$3 isolat\$3 oxide)) near12 (SiN SiON (silicon adj2 (oxynitride nitride)) Si3N4 "Si.sub.3N.sub.4" "Si.sub.3 N.sub.4" "SiN?sub.?")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/18 11:36

L9	55	7 and 8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/18 11:37
L10	13927	(anneal\$3 heat\$3 bak\$3 thermal thermally) near12 (SiN (silicon adj2 nitride) Si3N4 "Si.sub.3N.sub.4" "SiN?sub.?")	USPAT; EPO; JPO	OR	OFF	2004/11/18 11:50
L11	249	7 and 10	USPAT; EPO; JPO	OR	OFF	2004/11/18 11:50
L12	43	11 and 8	USPAT; EPO; JPO	OR	OFF	2004/11/18 11:50